

3.2 Tecnologia de Vácuo

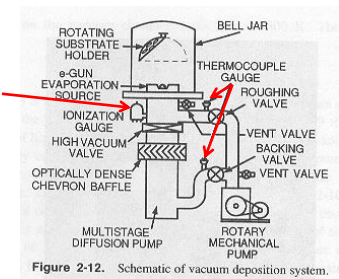
Prof. José Humberto Dias da Silva
Ciência e Tecnologia de Filmes Finos
POSMAT – Unesp/Bauru

- (a) Medidores de pressão
 - (b) Analisadores de gases
 - (c) Regimes de escoamento
-
- 3.3 (a) Medidores de Fluxo
 - 3.3 (b) Vazão e veloc. de bombeamento
 - 3.3 (c)Exercícios – Cap. 3

1

- 3.2 (a) Medidores de pressão

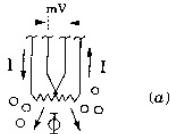
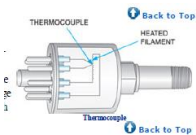
2



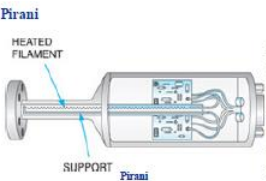
KJL Tecninical notes

(língua de sogra)

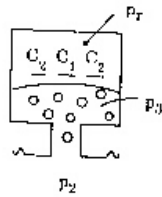
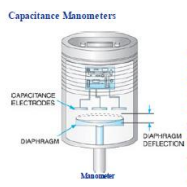
termopar



$$p_{\text{ATM}}-10^{-2}\text{torr}$$

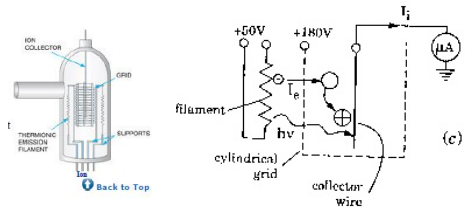


capacitância

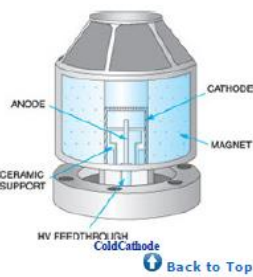


$1 - 10^{-4}$ torr

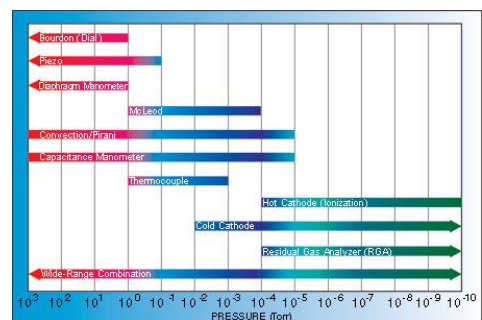
Iônico / Hot filament



$10^{-3} - 10^{-11}$ torr



Range – medidores de pressão



Medidores de Pressão

Conclusão:

* os medidores de pressão (vácuo) têm suas escalas típicas.

- Medidores de pressão
- 3.2 (b) Analisadores de gases
- Regimes de escoamento
- Medidores de Fluxo
- Exercícios – Cap. 3

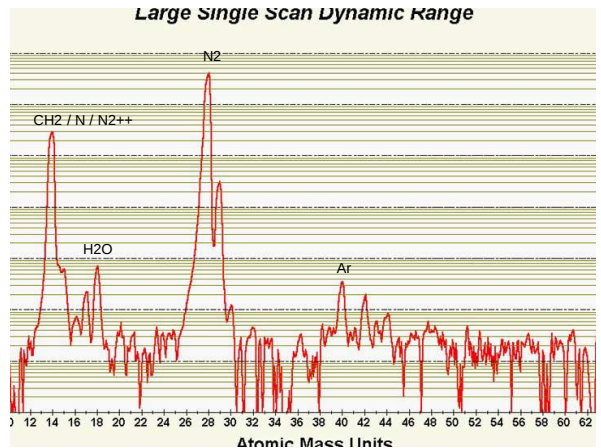
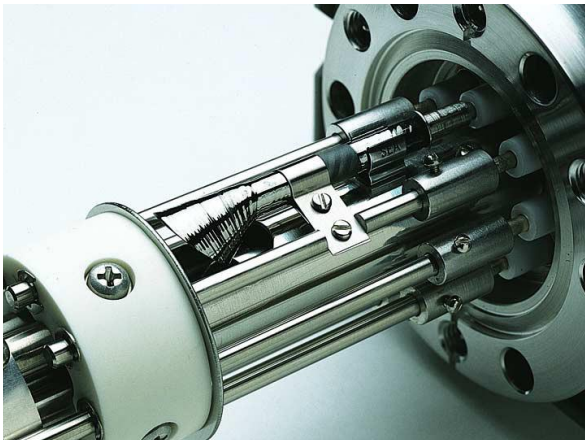
Analizador de gases residuais



- 100, 200 and 300 amu systems
- Better than 1 amu resolution
- 6 decades of dynamic range
- 5×10^{-14} Torr detection limit
- RGA Windows & LabVIEW software
- Field-replaceable electron multiplier and filament
- RS-232 interface

$$p_{\text{res}} \sim 10^{-2} - 10^{-12} \text{ torr}$$

Analizador de gases residuais



- Medidores de pressão
- Analísadores de gases
- 3.2 (c) Regimes de escoamento
- Medidores de Fluxo
- Exercícios – Cap. 3

Regimes de Escoamento

$$K_n = l/L$$

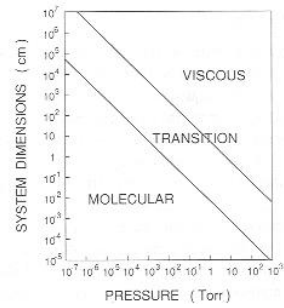
l = livre caminho médio

L = tamanho do sistema

Número de Knudsen:

- $Kn > 1$ – alto vácuo, colisões molécula-paredes **(molecular)**
- $Kn \ll 0,01$ – fluxo de fluido, colisões molécula-molécula **(fluido / viscoso)**
- $0.01 < Kn < 1$ – regime intermediário

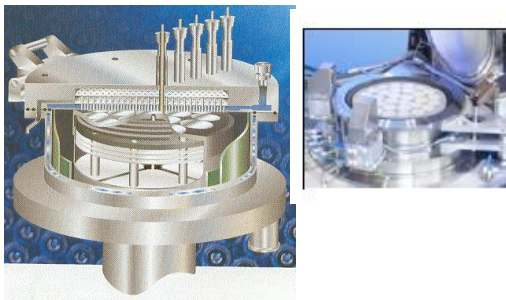
19



Regimes de fluxo de gás dominantes em função das dimensões do sistema e pressão

20

Reator CVD complexo (comercial)



21

Fluxo de gás / Inhomogeneidades

322 Chemical Vapor Deposition

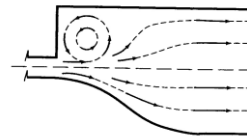


Figure 7.7 Two alternative reactor-entrance geometries patterns (upper and lower halves). The upper pattern avoided.

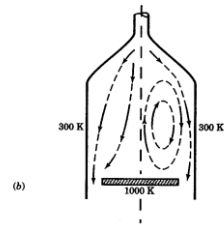


Figure 7.12 Typical free-convection roll cells: (a) horizontal rectangular-tube reactor (view along axis) with two alternate sidewall conditions, insulated (left) and cooled (right); (b) downflow axisymmetric reactor, showing two alternate flow patterns. In (b), the recirculating pattern (right) is to be avoided.

22

Distribuição de velocidades nas proximidades do susceptor (porta substratos).

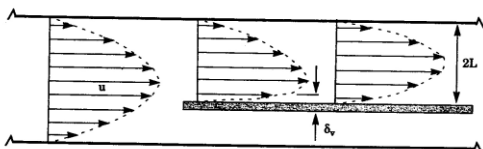


Figure 7.8 Velocity boundary layer of width δ_v forms at the susceptor leading edge in a tube reactor.

23

Linhas de fluxo de gás / simetria axial

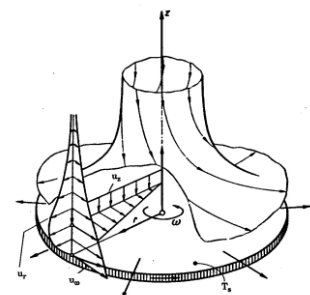


Figure 7.10 Axisymmetric flow pattern over a rotating disc. (Source: Reprinted from Ref. 7 by permission, © 1968 by McGraw-Hill Book Co.)

24

3.3 Tecnologia de Vácuo

- Medidores de pressão
- Analisadores de gases
- Regimes de escoamento
- 3.3 (a) Controladores de Fluxo
- Vazão e velocidade de bombeamento
- Exercícios – Cap. 3

25

Rotâmetro



<https://www.youtube.com/watch?v=BfdwD1V3jNk>

(mesmo que o do eletrônico)

26



fluxo ~ 0.1 – 200 sccm

<https://www.youtube.com/watch?v=BfdwD1V3jNk>

(mesmo que o do rotâmetro)

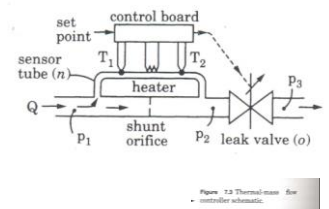
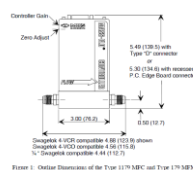


Figure 1.2 Thermal-mass flow controller schematic.

fluxo ~ 0.1 – 200 sccm

- Medidores de pressão
- Analisadores de gases
- Regimes de escoamento
- Controladores de Fluxo
- 3.3(b) Vazão e veloc. de bombeamento
- => novo arquivo 3.3

29

=> Apresentação 3.3